

### **REMARKS**

Claims 1-31 are pending in the application. Claims 1 and 11-15 have been amended, and claims 32-38 have been cancelled. Claims 32-38 are cancelled without prejudice in view of the restriction requirement of September 21, 2007. No new matter has been introduced by the amendment.

#### **Claim Objections**

An objection has been raised to claims 1, 11, 13 and 15 in view of various matters of form. This objection is overcome in view of the amendment of claims 1, 11, 13 and 15. In particular, claim 1 has been amended to strike the phrase "first and second" before "substrates" and replace the designation by the word "two." Claim 1 has been further amended to improve the form of the preamble and to include the transition "comprising." Claim 11 has been amended to remove the parenthetical following the term "oxide layer." Claim 13 has been amended to replace the term "given" with the term "predetermined." Claim 15 has been amended to remove the language "selected from the group," and now recites that the material comprises one or more of the listed alternatives.

The Applicants assert that the foregoing amendments address the claim objections and respectfully requests that these objections be withdrawn.

#### **Rejection Under 35 U.S.C. § 112, ¶ 2**

Claims 1, 11, 12 and 14 have been rejected for allegedly reciting vague subject matter. This rejection is believed overcome in view of the amendment of claim 11 and 12, together with the following remarks.

Claim 1 has been rejected in view of its recitation of "bulk regions" and "stacked regions." The Office Action alleges that it is unclear from the Applicants' figures as to the identification of the recited subject matter. The Applicants respectfully assert that the bulk regions and the stacked regions are disclosed in the Applicants' specification and depicted in the Applicants' drawing. For example, on page 5 of the English

translation of the published PCT Application, the Applicants describe a face-to-face relationship of two substrates in which the substrates are adjoined to one another. In regions where each face is essentially a crystalline material, such regions are identified as "bulk regions." (Pg. 5, lines 2-15.) Correspondingly, in regions in which at least one of the faces consists of a different material, such regions are designated as "stacked regions." Referring to FIGs. 4-6 of the Applicants' drawing, the bulk regions and stacked regions are designated as "Z2" and "Z1," respectively. As described by the Applicants on page 19 of the English translation and published PCT Application, SOI regions are delimited by regions Z1 and bulk regions of silicon-silicon contact are delimited by the regions Z2. (Pg. 19, lines 1-7). Other embodiments of the Applicants' invention are illustrated in FIGs. 7-34, in which a similar designation of stacked regions and bulk regions are provided. Accordingly, the Applicants assert that claim 1 clearly recites structure corresponding to that described and illustrated in various embodiments of the specification and drawing.

Claim 11 has been rejected for referring to mask patterns that are "not further apart" than the predetermined distance. This rejection is overcome in view of the amendment of claim 11 in which pattern features are recited that are laterally spaced apart by a distance of no more than the predetermined distance.

Claim 12 has been rejected for failure to provide antecedent basis for the term "preparation." This rejection is overcome in view of the amendment in which preparation has been changed to the phrase "providing two substrates."

Claim 14 has been rejected for recitation of language similar to that of claim 11. Accordingly, claim 14 has been similarly amended to recite that the pattern features are laterally spaced apart by a distance of no more than the predetermined distance. Claim 14 has been further amended to remove an inadvertent parenthetical following the term "thermal oxide layer."

#### **Drawing Correction**

The Applicants have amended the drawing to correct an inadvertent error in the designation of the substrate illustrated in FIG. 8. As set forth in the Applicants' English

translation of the PCT published application, the starting wafer illustrated in FIGs. 8 to 14 is designated as element 20. (Pg. 19, lines 25-33). Accordingly, the Applicants have corrected sheet 2/6 of the Applicants' drawing to reflect the correct element number for the designated starting wafer.

**Allowable Subject Matter**

The Office Action indicates that claims 1 and 11-15 would be allowable if rewritten to overcome the rejections and objections set forth in the Office Action. The Applicants assert that all of the objections and rejections have been addressed by the claim amendments set forth herein. Accordingly, the Applicants assert the amended claims are in condition for allowance.

The Office Action further states that claims 2-10 and 16-31 are objectionable because they are dependent upon rejected base claims. The Applicants assert that rejection of the base claims has been overcome and, accordingly, claims 2-10 and 16-31 are now in condition for allowance.

The Applicants have made a novel and nonobvious contribution to the art of mix substrate fabrication. The claims at issue distinguish over the prior art and are in condition for allowance. Accordingly, such allowances are now earnestly requested.

Respectfully submitted,

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"ANNNOTATED SHEET"

